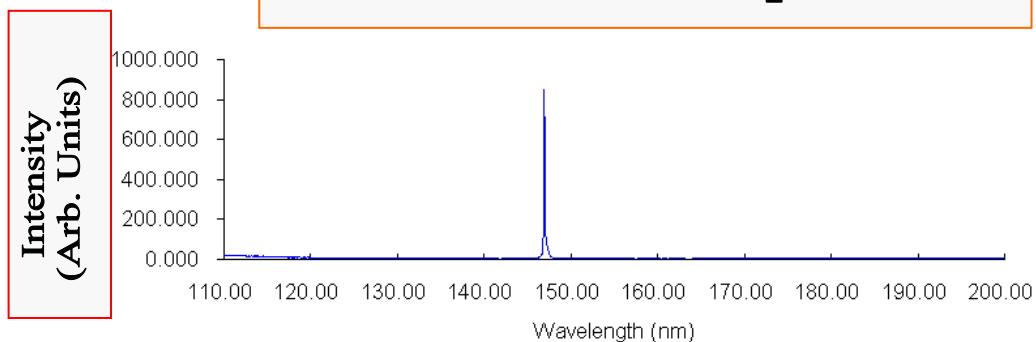


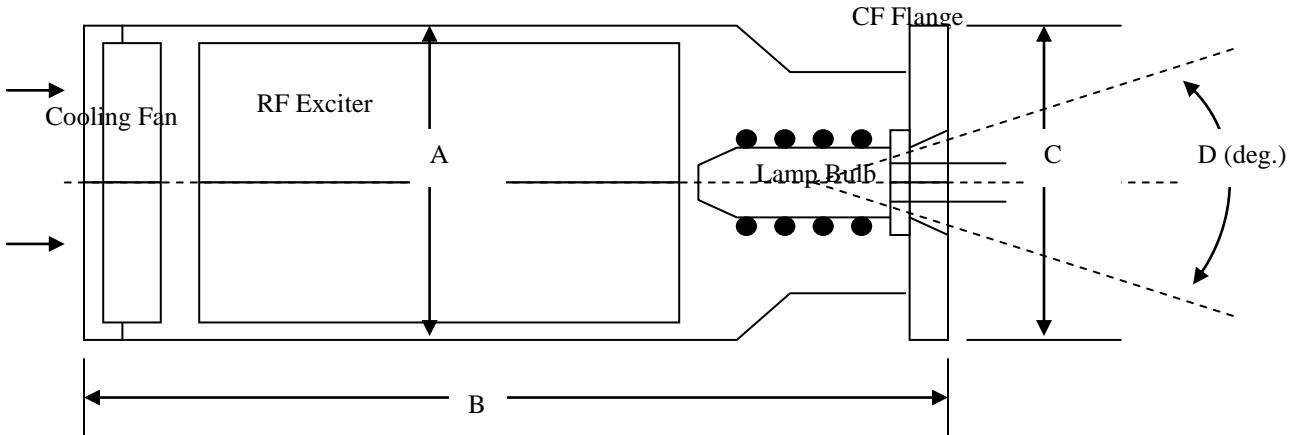
Model No:	Description:
XeLM-LHP	<p>High Power Xenon Vacuum Ultraviolet (VUV) Line Source</p> <p>This Xenon filled RF powered lamp system is a reliable and maintenance free high intensity source of deep VUV emissions at 147.0 NM. This source mounts to a 6 inch CF flange or Acton/Mcpherson flange for convenient connection to a UHV system. VUV fluxes greater than 100milliwatts are delivered through the output window for use in vacuum applications such as photoionization, photolithography and mass spectroscopy.</p>

Electrical /Optical Specifications/General:				
Specification	Minimum	Typical	Maximum	units
Gas Fill		Xenon		na
Peak wavelengths	-	147.0	-	NM
Full Spectral Range	-	116.5 to 7,000	-	NM
VUV Intensity	5×10^{16}	5×10^{17}	-	Photons/sec/sr
Full angle output cone	30	45	65	Degrees
Window Material		MgF ₂		na
Clear Aperture of window	0.4		1.8	CM.
Pulse	Modulation to 1 kz available as option			
Certification	NIST Traceable Calibration of Irradiance in Vacuum			
Plasma depth behind face of front flange	2.0	3.0	4.0	CM.
Plasma diameter	0.9		4	CM.
Plasma length	3		10	CM.
Input Power	25	75	120	Watts
Input voltage	70	115	260	VAC
Input Line Frequency	50	60	65	Hz
Mounting flange	6 inch Conflat is standard, lamp can be sealed to UHV system			
Cooling	Forced air cooling with internal fan			
Intensity monitor	Intensity monitor available as an option			
Thermal control	na			
System	Complete system includes power supply, EMI shielded enclosure, Vacuum flange and NIST Traceable calibration			

Xe VUV Line Spectrum



Mechanical Specifications (configuration A)



Dimension	Value	Unit
A	6.0	Inches
B	21.0 (Max)	Inches
C	6.0 (Max)	Inches
D	45 (Typ.)	Degrees
Tolerances	±0.005	Inches
Materials		
Window	Magnesium Flouride	
Body	Aluminum	
Mass	5 kg.	
Vacuum Adapters	Stainless Steel	

